

**REMARKS**

Applicant thanks the Examiner for the thorough review and consideration of the present application. The final Office Action dated October 17, 2003 has been received and its contents carefully reviewed.

By this Response, Applicant has amended claim 28. No new matter has been added. Claims 18-41 are pending in the application with claims 18-27 being allowed. Reconsideration and withdrawal of the rejection of claims 28-41 are requested.

In the Office Action, claims 28-41 are rejected under 35 U.S.C. § 103(a) as being unpatentable over U.S. Patent No. 6,445,428, issued to Fujikawa et al. (hereafter "Fujikawa") in view of U.S. Patent No. 6,177,970, issued to Kim. Applicant traverses the rejection because neither Fujikawa nor Kim, analyzed alone or in any combination, teach or suggest the combined features recited in the claims of the present application. In particular, Fujikawa and Kim fail to teach or suggest a method of manufacturing an in-plane switching mode liquid crystal display (LCD) device that includes, "forming source and drain electrodes connected with the pixel electrodes on the buffer layer" as recited in independent claim 28 and its dependent claims 29-41 of the present application.

Fujikawa discloses a fabrication process for a thin film transistor for use in a liquid crystal display device in which the thin-film transistor has "a protective insulation film covering said thin-film transistor and a pixel electrode provided on said protective insulation film in electrical connection with said thin-film transistor" (col. 3, lines 24-32). In FIG. 4 of Fujikawa, the amorphous silicon pattern 26A or 26B are formed "underneath the barrier metal layer" (27a or 27d, respectively) (see, col. 8, lines 23-26 and FIG. 4). And, a pixel electrode 29 is formed on the protective insulation film 28 and has a point of contact with conductor layer 27e. Applicant respectfully notes that the source and drain electrodes, 408 and 409 respectively, as recited in claim 28 and illustrated in FIG. 3 of the present application, are formed on the buffer layer 406, and the pixel electrode 407 is formed on the buffer layer 406. Thus, Fujikawa fails to teach or recite the combined features recited in claim 28 and its dependent claims 29-41 of the present application.

In Kim, as illustrated in FIG. 2, the source 710 and drain 720 are formed directly on the ohmic contact layers 611 and 612, and the pixel electrode 40 is formed on the passivation layer

80. Thus, Kim, like Fujikawa, fails to teach or suggest the combined features recited in independent claim 28.

Because Kim fails to teach or suggest the combined features recited in claim 28, one of ordinary skill in the art would not be motivated to modify the method of Fujikawa by the method disclosed in Kim to obtain a method of manufacturing an in-plane switching mode liquid crystal display (LCD) that includes "forming source and drain electrodes connected with the pixel pixel electrode on the buffer layer", as recited in claim 28. Accordingly, independent claim 28 and its dependent claims 29-41 are patentable over Fujikawa and Kim. Reconsideration and withdrawal of the rejection are requested.

In view of the above, Applicant respectfully submits the pending claims are in condition for allowance. Should the Examiner deem that a telephone conference would further the prosecution of this application, the Examiner is invited to contact the undersigned at the number indicated.

Application No. 10/020,891  
Amendment dated January 20, 2004  
Reply to Office Action of October 17, 2003

Docket No.: 8733.495.00-US

If these papers are not considered timely filed by the Patent and Trademark Office, then a petition is hereby made under 37 CFR § 1.136, and any additional fees required under 37 CFR §1.136 for any necessary extension of time, or any other fees required to complete the filing of this response, may be charged to Deposit Account No. 50-0911. Please credit any overpayment to Deposit Account No. 50-0911. A duplicate copy of this sheet is enclosed.

Dated: January 20, 2004

Respectfully submitted,

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